Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S30	1866	mercaptothiadiazole	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/09 15:58
S32	8	mercapto with thiadiazole and copper adj (plating electroplating)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/09 17:11
S31	3	mercaptothiadiazole and copper adj (plating electroplating)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/09 17:11
S1 ,	3	"6709652".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 13:40
L3	182	suppressor and copper adj electroplating	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 13:40
L2	0	suppressor and copper adj electroplatin	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 13:40
L4	168	suppressor and copper adj electroplating and (semiconductor wafer microelectronic)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 13:41
S21	<b>52</b>	suppressor with polyether	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 13:42
L6	8170	polyether and (semiconductor wafer microelectronic)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 13:44

L5	18	leveler with polyether	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 13:44
L7	126	polyether same (supressor suppressor supresor leveler leveller leveling) and (semiconductor wafer microelectronic)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 13:57
L8	21	sulfonopropyl adj disulfide	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 13:58
L9	2	"6113771".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 13:59
L10	2	"6379522".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 14:01
L16	0	bissulfonopropyl adj disulfide	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 14:02
L15	21	sulfonopropyl adj disulfide	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 14:02
L14	3	sulfonopropyl\$1disulfide	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 14:02
L13	0	bis\$1sulfonopropyl\$1disulfide	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 14:02
L12	O	"bis\$1sulfonopropyl\$1disulfide"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 14:02

L11	21	"bis-sodium-sulfonopropyl-disulfid e"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 14:02
L17	0	bis adj sulfonopropyl adj disulfide	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 14:03
L20	11	("3770598" "4374709" "4376685" "4555315" "4673469").pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 14:06
L19	2	"3778357".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 14:06
L18	21	bis adj sodium adj sulfonopropyl adj disulfide	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 14:19
L22	161	sulfopropyl with disulfide	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 14:20
L21	14	bis adj sodium adj sulfopropyl adj disulfide	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 14:20
L24	26	(ULSI vLSI) and Creutz	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 14:41
L27	147	26 and (suppresor suppressor supresor supressor)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 14:52
L26	1631	(sulfate acid) with copper with electroplating	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 14:52

L29	53	26 and (suppresor suppressor supresor supressor) same (polyethylene adj glycol)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 14:55
L28	41	26 and (suppresor suppressor supresor supressor) same (polyether)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 14:55
L30	147	26 and (suppresor suppressor supresor supressor)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 14:56
L33	46623	(suppressor carrier) with (ether glycol)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 15:11
L32	68646	(suppressor carrier) same (ether glycol)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 15:11
L31	6	("4,347,108" "4,673,469" "4,683, 036").pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 15:11
S3	2	cretz	USOCR	OR	ON	2005/05/12 16:35
L44	93	creutz	USOCR	OR	ON	2005/05/12 16:35
L34	7	(suppressor carrier) with (ether glycol) and 205/157.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 16:40
L47	2	"5,252,196".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 17:06
L45	21	(suppressor carrier) with (ether glycol) and 205/296.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 17:06

L52	181	sulfopropyl same disulfide	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 18:14
L23	116	sulfopropyl same disulfide and copper with electroplating	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 18:14
L54	29215	(benzene adj sulfonic benzene\$1sulfonic)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 18:35
L53	62	sulfopropyl same disulfide same brighten\$3 and copper with electroplating	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 18:35
L56		"2,424,887".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/12 18:37
L55	22	(benzene adj sulfonic benzene\$1sulfonic) and copper adj electroplating	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ÖR	ON	2005/05/12 18:37